

"HELP COMMANDS" at an arrow prompt (=>).

=> file pnetext

'PNETEXT' IS NOT A VALID FILE NAME

SESSION CONTINUES IN FILE 'HOME'

Enter "HELP FILE NAMES" at an arrow prompt (=>) for a list of files that are available. If you have requested multiple files, you can specify a corrected file name or you can enter "IGNORE" to continue accessing the remaining file names entered.

=> file pntttext

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

0.63

0.63

FILE 'EUROPATFULL' ENTERED AT 13:42:48 ON 22 FEB 2004

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FILE 'USPAT2' ENTERED AT 13:42:48 ON 22 FEB 2004

CA INDEXING COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

=> s Yoshida, Kiyoshi/in

'IN' IS NOT A VALID FIELD CODE

L1 86 YOSHIDA, KIYOSHI/IN

=> s l1 and polyphenylene ether resin#

L2 4 L1 AND POLYPHENYLENE ETHER RESIN#

=> d l2 1-4

L2 ANSWER 1 OF 4 EUROPATFULL COPYRIGHT 2004 WILA on STN

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 1209183 EUROPATFULL ED 20020607 EW 200222 FS OS

TIEN METHOD OF PRECIPITATING POLYPHENYLENE ETHER.

TIDE VERFAHREN ZUR FAELLUNG VON POLYPHENYLENETHER.

TIFR PROCEDE DE PRECIPITATION D'UN POLYPHENYLENE ETHER.

IN YOSHIDA, Kiyoshi Yokkaichi Plant, Mitsubishi Gas Chem. Co. Inc.

2-4-16 Hinagahigashi, Yokkaichi-shi Mie 510-0886, JP;

OHSAKI, Naoto Yokkaichi Plant, Mitsubishi Gas Chem. Co. Inc. 2-4-16

Hinagahigashi, Yokkaichi-shi Mie 510-0886, JP;

FUJII, Hiroya Yokkaichi Plant, Mitsubishi Gas Chem. Co. Inc. 2-4-16

Hinagahigashi, Yokkaichi-shi Mie 51-0886, JP

PA MITSUBISHI GAS CHEMICAL COMPANY, INC., 5-2, Marunouchi 2-chome,

Chiyoda-Ku, Tokyo 100-0005, JP

SO Wila-EPZ-2002-H22-T1a

DS R AT; R BE; R CH; R CY; R DE; R DK; R ES; R FI; R FR; R GB; R GR; R IE;

R IT; R LI; R LU; R MC; R NL; R PT; R SE

PIT EPA1 EUROPAEISCHE PATENTANMELDUNG (Internationale Anmeldung)

PI EP 1209183

A1 20020529

OD 20020529
 AI EP 2000-922910 20000428
 RLI WO 00-JP2834 000428 INTAKZ
 WO 0183586 011108 INTPNR
 IC ICM C08G065-46
 ICS C08J003-14

L2 ANSWER 2 OF 4 EUROPATFULL COPYRIGHT 2004 WILA on STN

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 1207175 EUROPATFULL ED 20020605 EW 200221 FS OS
 TIEN PROCESS FOR PRODUCING POLYPHENYLENE ETHER.
 TIDE VERFAHREN ZUR HERSTELLUNG VON POLYPHENYLETHER.
 TIFR PROCEDE DE PRODUCTION D'UN POLYPHENYLENE ETHER.
 IN YOSHIDA, Kiyoshi, 4-16, Hinagahigashi 2-chome, Yokkaichi-shi, Mie
 510-0886, JP;
 OHSAKI, Naoto, 4-16, Hinagahigashi 2-chome, Yokkaichi-shi, Mie 510-0886,
 JP;
 FUJII, Hiroya, 4-16, Hinagahigashi 2-chome, Yokkaichi-shi, Mie 510-0886,
 JP
 PA MITSUBISHI GAS CHEMICAL COMPANY, INC., 5-2, Marunouchi 2-chome,
 Chiyoda-Ku, Tokyo 100-0005, JP
 SO Wila-EPZ-2002-H21-T1a
 DS R AT; R BE; R CH; R CY; R DE; R DK; R ES; R FI; R FR; R GB; R GR; R IE;
 R IT; R LI; R LU; R MC; R NL; R PT; R SE
 PIT EPA1 EUROPAEISCHE PATENTANMELDUNG (Internationale Anmeldung)
 PI EP 1207175 A1 20020522
 OD 20020522
 AI EP 2000-921097 20000428
 RLI WO 00-JP2835 000428 INTAKZ
 WO 0183587 011108 INTPNR
 IC ICM C08G065-46
 ICS C08G065-44 C08J003-14

L2 ANSWER 3 OF 4 PCTFULL COPYRIGHT 2004 Univentio on STN

Full
Text

AN 2001083587 PCTFULL ED 20020826
 TIEN PROCESS FOR PRODUCING POLYPHENYLENE ETHER
 TIFR PROCEDE DE PRODUCTION D'UN POLYPHENYLENE ETHER
 IN YOSHIDA, Kiyoshi;
 OHSAKI, Naoto;
 FUJII, Hiroya
 PA MITSUBISHI GAS CHEMICAL COMPANY, INC.;
 YOSHIDA, Kiyoshi;
 OHSAKI, Naoto;
 FUJII, Hiroya
 DT Patent
 PI WO 2001083587 A1 20011108
 DS W: SG US AT BE CH CY DE DK ES FI FR GB GR IE IT LU MC NL PT
 SE
 AI WO 2000-JP2835 A 20000428
 ICM C08G065-46
 ICS C08G065-44; C08J003-14

L2 ANSWER 4 OF 4 USPATFULL on STN

Full
Text

Citing
References

AN 2003:260796 USPATFULL
 TI Method of precipitating polyphenylene ether
 IN Yoshida, Kiyoshi, Yokkaichi, JAPAN
 Ohsaki, Naoto, Yokkaichi, JAPAN
 Fujii, Hiroya, Yokkaichi, JAPAN

PA Mitsubishi Gas Chemical Co, Tokyo, JAPAN (non-U.S. corporation)
 PI US 6627727 B1 20030930
 WO 2001083586 20011108
 AI US 2001-19072 20011226 (10)
 WO 2000-JP2834 20000428
 DT Utility
 FS GRANTED
 LN.CNT 284
 INCL INCLM: 528/491.000
 INCLS: 528/495.000; 528/496.000; 528/498.000; 528/502.000R; 528/502.000A
 NCL NCLM: 528/491.000
 NCLS: 528/495.000; 528/496.000; 528/498.000; 528/502.000A; 528/502.000R
 IC [7]
 ICM: C08G065-46
 ICS: C08J003-14
 EXF 528/491; 528/495; 528/496; 528/498; 528/502R; 528/502A
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

=> s phenol and oxidative polymeriz? and copper compound#
 L3 22 PHENOL AND OXIDATIVE POLYMERIZ? AND COPPER COMPOUND#

=> s 13 and amine#
 L4 20 L3 AND AMINE#

=> s 14 and precipitat?
 L5 20 L4 AND PRECIPITAT?

=> s 15 and methanol#
 L6 20 L5 AND METHANOL#

=> s 16 and solid-liquid separat?
 L7 3 L6 AND SOLID-LIQUID SEPARAT?

=> s 17 and liquid-liquid separat?
 L8 1 L7 AND LIQUID-LIQUID SEPARAT?

=> d

L8 ANSWER 1 OF 1 EUROPATFULL COPYRIGHT 2004 WILA on STN

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 1207175 EUROPATFULL ED 20020605 EW 200221 FS OS
 TIEN PROCESS FOR PRODUCING POLYPHENYLENE ETHER.
 TIDE VERFAHREN ZUR HERSTELLUNG VON POLYPHENYLETHER.
 TIFR PROCEDE DE PRODUCTION D'UN POLYPHENYLENE ETHER.
 IN YOSHIDA, Kiyoshi, 4-16, Hinagahigashi 2-chome, Yokkaichi-shi, Mie
 510-0886, JP;
 OHSAKI, Naoto, 4-16, Hinagahigashi 2-chome, Yokkaichi-shi, Mie 510-0886,
 JP;
 FUJII, Hiroya, 4-16, Hinagahigashi 2-chome, Yokkaichi-shi, Mie 510-0886,
 JP
 PA MITSUBISHI GAS CHEMICAL COMPANY, INC., 5-2, Marunouchi 2-chome,
 Chiyoda-Ku, Tokyo 100-0005, JP
 SO Wila-EPZ-2002-H21-T1a
 DS R AT; R BE; R CH; R CY; R DE; R DK; R ES; R FI; R FR; R GB; R GR; R IE;
 R IT; R LI; R LU; R MC; R NL; R PT; R SE
 PIT EPA1 EUROPAEISCHE PATENTANMELDUNG (Internationale Anmeldung)
 PI EP 1207175 A1 20020522
 OD 20020522
 AI EP 2000-921097 20000428
 RLI WO 00-JP2835 000428 INTAKZ

WO 0183587 011108 INTPNR
IC ICM C08G065-46
ICS C08G065-44 C08J003-14

=> d 17 1-3

L7 ANSWER 1 OF 3 EUROPATFULL COPYRIGHT 2004 WILA on STN

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 1207175 EUROPATFULL ED 20020605 EW 200221 FS OS
TIEN PROCESS FOR PRODUCING POLYPHENYLENE ETHER.
TIDE VERFAHREN ZUR HERSTELLUNG VON POLYPHENYLETHER.
TIFR PROCEDE DE PRODUCTION D'UN POLYPHENYLENE ETHER.
IN YOSHIDA, Kiyoshi, 4-16, Hinagahigashi 2-chome, Yokkaichi-shi, Mie
510-0886, JP;
OHSAKI, Naoto, 4-16, Hinagahigashi 2-chome, Yokkaichi-shi, Mie 510-0886,
JP;
FUJII, Hiroya, 4-16, Hinagahigashi 2-chome, Yokkaichi-shi, Mie 510-0886,
JP
PA MITSUBISHI GAS CHEMICAL COMPANY, INC., 5-2, Marunouchi 2-chome,
Chiyoda-Ku, Tokyo 100-0005, JP
SO Wila-EPZ-2002-H21-T1a
DS R AT; R BE; R CH; R CY; R DE; R DK; R ES; R FI; R FR; R GB; R GR; R IE;
R IT; R LI; R LU; R MC; R NL; R PT; R SE
PIT EPA1 EUROPAEISCHE PATENTANMELDUNG (Internationale Anmeldung)
PI EP 1207175 A1 20020522
OD 20020522
AI EP 2000-921097 20000428
RLI WO 00-JP2835 000428 INTAKZ
WO 0183587 011108 INTPNR
IC ICM C08G065-46
ICS C08G065-44 C08J003-14

L7 ANSWER 2 OF 3 EUROPATFULL COPYRIGHT 2004 WILA on STN

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 255230 EUROPATFULL ED 20001015 EW 198805 FS OS STA B
TIEN Process for producing polyphenylene ethers.
TIDE Verfahren zur Herstellung von Polyphenylenethern.
TIFR Procede de preparation de poly(ethers de phenylene).
IN Abe, Katsuhiko, 23-18, Hagigaoka-cho, Yokkaichi-shi Mie, JP;
Yano, Kazunori, 4-5-53-102, Ogoso, Yokkaichi-shi Mie, JP;
Matsui, Ryuhei, 129, Sasagawa 7-chome, Yokkaichi-shi Mie, JP;
Kiriya, Shigeki, 4025-12, Takajaya Komori-cho, Tsu-shi Mie, JP;
Tatsukami, Yioshiharu, 2-8-2, Kita Sakurazuka, Toyonaka-shi Osaka, JP;
Nagaoka, Kenji, 81-18, Ikaga Nishimachi, Hirakata-shi Osaka, JP
PA MITSUBISHI PETROCHEMICAL CO., LTD., 5-2, 2-chome, Marunouchi, Chiyoda-ku
Tokyo 100, JP;
SUMITOMO CHEMICAL COMPANY, LIMITED, 15 Kitahama 5-chome Higashi-ku,
Osaka-shi Osaka 541, JP
SO Wila-EPZ-1988-H05-T1
DS R BE; R DE; R FR; R GB; R IT; R NL
PIT EPA1 EUROPAEISCHE PATENTANMELDUNG
PI EP 255230 A1 19880203
OD 19880203
AI EP 1987-305663 19870625
PRAI JP 1986-148700 19860625
IC ICM C08G065-46
ICS C08J003-12

GRANTED PATENT - ERTEILTES PATENT - BREVET DELIVRE

AN 255230 EUROPATFULL UP 20020207 EW 199242 FS PS STA B
TIEN Process for producing polyphenylene ethers..
TIDE Verfahren zur Herstellung von Polyphenylenethern.
TIFR Procède de preparation de poly(ethers de phenylene).
IN Abe, Katsuhiko, 23-18, Hagigaoka-cho, Yokkaichi-shi Mie, JP;
Yano, Kazunori, 4-5-53-102, Ogozo, Yokkaichi-shi Mie, JP;
Matsui, Ryuhei, 129, Sasagawa 7-chome, Yokkaichi-shi Mie, JP;
Kiriyaama, Shigeki, 4025-12, Takajaya Komori-cho, Tsu-shi Mie, JP;
Tatsukami, Yioshiharu, 2-8-2, Kita Sakurazuka, Toyonaka-shi Osaka, JP;
Nagaoka, Kenji, 81-18, Ikaga Nishimachi, Hirakata-shi Osaka, JP
PA MITSUBISHI PETROCHEMICAL CO., LTD., 5-2, 2-chome, Marunouchi, Chiyoda-ku
Tokyo 100, JP;
SUMITOMO CHEMICAL COMPANY, LIMITED, Kitahama 4-chome 5-33, Chuo-ku Osaka
541, JP
SO Wila-EPS-1992-H42-T1
DS R BE; R DE; R FR; R GB; R IT; R NL
PIT EPB1 EUROPAEISCHE PATENTSCHRIFT
PI EP 255230 B1 19921014
OD 19880203
AI EP 1987-305663 19870625
PRAI JP 1986-148700 19860625
REP EP 116442 A CA 1015496 A
GB 2025440 A US 4263426 A
IC ICM C08G065-46
ICS C08J003-12

L7 ANSWER 3 OF 3 USPATFULL on STN

	Full Text	Citing References
AN	90:6073	USPATFULL
TI	Process for producing polyphenylene ether, dispersing polyether in aqueous medium and heating dispersion	
IN	Abe, Katsuhiko, Mie, Japan Yano, Kazunori, Mie, Japan Matsui, Ryuhei, Mie, Japan Kiriyaama, Shigeki, Mie, Japan Tatsukami, Yoshiharu, Osaka, Japan Nagaoka, Kenji, Osaka, Japan	
PA	Mitsubishi Petrochemical Co., Ltd., Tokyo, Japan (non-U.S. corporation) Sumitomo Chemical Company, Ltd., Osaka, Japan (non-U.S. corporation)	
PI	US 4895929	19900123
AI	US 1987-66295	19870625 (7)
PRAI	JP 1986-148700	19860625
DT	Utility	
FS	Granted	
LN.CNT	518	
INCL	INCLM: 528/487.000 INCLS: 528/212.000; 528/214.000; 528/486.000; 528/490.000; 528/495.000; 528/496.000; 528/499.000	
NCL	NCLM: 528/487.000 NCLS: 528/212.000; 528/214.000; 528/486.000; 528/490.000; 528/495.000; 528/496.000; 528/499.000	
IC	[4] ICM: C08G065-46	
EXF	528/487; 528/486; 528/490; 528/495; 528/496; 528/499; 528/212; 528/214	
CAS	INDEXING IS AVAILABLE FOR THIS PATENT.	

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